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INFORMATION DISCLOSURE STATEMENT
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Applicant: VAN SANTEN et al.
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Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
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	BR	6,603,130	08/2003	BISSCHOPS et al.	250	492.1	
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						Enclosed	No	Enclosed	No
HN	JR	JP 07-220990	08/1995	JAPAN	FUKUDA et al.	X			
	KR	JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
	LR	JP 10-255319	09/1998	JAPAN	SUENAGA et al.	X			
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HN	VR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
	WR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			
	XR	B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269			
	YR	G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72			
	ZR	S. OWA et al., "Immersion Lithography: its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003			
HN	AAR	S. OWA et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)			

Examiner H. Nguyen Date Considered: 6/13/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.